

Title (en)
METAL MASK MATERIAL AND PRODUCTION METHOD THEREFOR

Title (de)
METALLMASKENMATERIAL UND HERSTELLUNGSVERFAHREN DAFÜR

Title (fr)
MATÉRIAU POUR MASQUE MÉTALLIQUE, ET PROCÉDÉ DE FABRICATION DE CELUI-CI

Publication
EP 3508285 A1 20190710 (EN)

Application
EP 17846646 A 20170831

Priority
• JP 2016169881 A 20160831
• JP 2017031349 W 20170831

Abstract (en)
Provided are: a metal mask material the shape change of which after etching is suppressed and which is preferable in order to achieve good resist adhesiveness and good etching workability; and a production method for the metal mask material. The metal mask material has a surface roughness in the rolling direction and a surface roughness in a direction perpendicular to the rolling direction, which satisfy $0.05\text{ }\mu\text{m}\leq\text{Ra}\leq0.25\text{ }\mu\text{m}$ and $\text{Rz}\leq1.5\text{ }\mu\text{m}$. The metal mask material has a skewness Rsk of 0 or greater in the direction perpendicular to the rolling direction. When a sample having a length of 150 mm and a width of 30 mm is cut out of the metal mask material and the thickness of the sample is reduced by 60% by etching from one side of the sample, the amount of warpage of the sample is 15 mm or less. The metal mask material has a thickness of 0.10-0.5 mm.

IPC 8 full level
B21B 1/22 (2006.01); **B21B 3/02** (2006.01); **C21D 9/46** (2006.01); **C22C 19/03** (2006.01); **C22C 38/00** (2006.01); **C22C 38/08** (2006.01); **C22F 1/00** (2006.01)

CPC (source: EP KR)
B21B 1/22 (2013.01 - EP KR); **B21B 3/02** (2013.01 - EP KR); **C21D 6/001** (2013.01 - EP); **C21D 9/0068** (2013.01 - EP); **C21D 9/46** (2013.01 - EP KR); **C22C 19/03** (2013.01 - EP KR); **C22C 38/00** (2013.01 - EP); **C22C 38/08** (2013.01 - EP KR); **C22F 1/00** (2013.01 - EP)

Cited by
EP3805415A1; EP4163407A1

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)
BA ME

DOCDB simple family (publication)
EP 3508285 A1 20190710; **EP 3508285 A4 20200513**; **EP 3508285 B1 20210929**; CN 109641248 A 20190416; CN 109641248 B 20210406; JP 6646882 B2 20200214; JP WO2018043642 A1 20190624; KR 102164912 B1 20201013; KR 20190030754 A 20190322; WO 2018043642 A1 20180308

DOCDB simple family (application)
EP 17846646 A 20170831; CN 201780052365 A 20170831; JP 2017031349 W 20170831; JP 2018537395 A 20170831; KR 20197005481 A 20170831